

Docket Number: 081468-0306525
Client Reference: P-1586.010-US

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re the Application of
Joeri LOF et al.
Application No.: 10/705,816

Group Art Unit:

Examiner: Unassigned

Filed: November 12, 2003

Confirmation No.: Unassigned

For: Lithographic Apparatus and Device Manufacturing Method

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
TL	Joeri LOF et al.	10/705,805	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
TL	Joeri LOF et al.	10/705,783	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
TL	Helmar VAN SANTEN et al.	10/743,271	12/23/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
TL	Johannes C.H. MULKENS et al.	10/743,266	12/23/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
TL	Antonius T.A.M. DERKSEN et al.	10/705,785	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
TL	Klaus SIMON et al.	10/724,402	12/01/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
TL	Arno J. BLEEKER	10/715,116	11/18/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
TL	Bob STREEFKERK et al.	10/719,683	11/24/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
TL	Joannes T. DeSMIT et al.	10/705,804	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card

*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

□□



Atty. Dkt. No.	M#	Client Ref.
081468	0306525	P-1586.010-US

**INFORMATION DISCLOSURE STATEMENT
 BY APPLICANT**

Applicant: Joeri LOF et al.
 Appln. No.: 10/705,816
 Filing Date: November 12, 2003
 Examiner: ~~Unassigned~~ Tony Lu Group Art Unit: ~~Unassigned~~ 2528

Date: February 20, 2004 Page 1 of 1

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
TL	AR 2004/0000627A1	01/01/2004	Karl-Heinz SCHUSTER			
TL	BR 6,600,547	07/29/2003	WATSON et al.			
TL	CR 2004/0021844 A1	02/05/2004	Yutaka SUENAGA			
	DR					
	ER					
	FR					
	GR					
	HR					
	IR					
	JR					
	KR					
	LR					
	MR					
	NR					

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
	OR							
	PR							
	QR							
	RR							
	SR							
	TR							
	UR							
	VR							
	WR							
	XR							

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

TL	YR	H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3			
TL	ZR	S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.			
	AAR				
	BBR				
	CCR				
	DDR				

Examiner: *[Signature]* Date Considered: 12/2005
 *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office

Atty. Dkt. No.	M#	Client Ref.
	306525	P-1586.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant:	Joeri LOF <i>et al.</i>
Appln. No.:	Unknown 10/205,816
Filing Date:	November 12, 2003
Examiner:	Unknown <i>any L</i> Group Art Unit: Unknown <i>3071</i>

Date: November 12, 2003 Page 1 of 3

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
TL	AR	3,573,975	04/1971	Dhaka <i>et al.</i>	117	212	
TL	BR	3,648,587	03/1972	Stevens	95	44	
TL	CR	4,346,164	08/1982	Tabarelli <i>et al.</i>	430	311	
TL	DR	4,396,705	08/1983	Akeyama <i>et al.</i>	430	326	
TL	ER	4,480,910	11/1984	Takanashi <i>et al.</i>	355	30	
TL	FR	4,509,852	04/1985	Tabarelli <i>et al.</i>	355	30	
TL	GR	5,040,020	08/1991	Rauschenbach <i>et al.</i>	355	53	
TL	HR	5,121,256	06/1992	Corle <i>et al.</i>	359	664	
TL	IR	5,610,683	03/1997	Takahashi	355	53	
TL	JR	5,715,039	02/1998	Fukuda <i>et al.</i>	355	53	
TL	KR	5,825,043	10/1998	Suwa	250	548	
TL	LR	5,900,354	05/1999	Batchelder	430	395	
TL	MR	6,191,429	02/2001	Suwa	250	548	
TL	NR	6,560,032	05/2003	Hatano	359	656	

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclose	No
TL	OR	WO 99/49504	09/1999	PCT	Fukami <i>et al.</i>	X		X	
TL	PR	EP 0023231	02/1981	Europe	Tabarelli <i>et al.</i>	X			
TL	QR	EP 0418427	03/1991	Europe	Miyake	X		X	
TL	RR	EP 1039511	09/2000	Europe	Murakimi <i>et al.</i>	X		X	
TL	SR	DD 224448	07/1985	German	Hesse <i>et al.</i>		X		
TL	TR	DD 242880	02/1987	German	Kuch		X		
TL	UR	FR 2474708	07/1981	France	Letellier		X		
TL	VR	JP 62-065326	03/1987	Japan	Moriuchi	X			
TL	WR	JP 62-121417	06/1987	Japan	Nakazawa	X			
TL	XR	JP 63-157419	06/1988	Japan	Nakasuji	X			

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

TL	YR	EP Search Report for EP 02257938 dated September 25, 2003			
TL	ZR	M. Switkes <i>et al.</i> , "Immersion Lithography at 157 nm", MIT Lincoln Lab, Orlando 2001-1, December 17, 2001			
TL	AAR	M. Switkes <i>et al.</i> , "Immersion Lithography at 157 nm", J. Vac. Sci. Technol. B., Vol. 19, No. 6, November/December 2001, pp. 2353-2356			
TL	BBR	M. Switkes <i>et al.</i> , "Immersion Lithography: Optics for the 50 nm Node", 157 Anvers-1, September 4, 2002			

Examiner	Date Considered: 12/2005
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.	

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office

Atty.
Dkt. No.

M#

Client Ref.

306781

P-0381.010-US

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: Joeri LOF *et al.*

Appln. No.: ~~Unknown~~ 10/705 816

Filing Date: November 12, 2003

Examiner: ~~Unknown~~ Tany Lu Group Art Unit: ~~Unknown~~ 2070

Date: November 12, 2003

Page

2

of

3

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
TL	CCR	6,603,130	08/2003	Bisschops <i>et al.</i>	250	492.1	
TL	DDR	6,633,365	10/2003	Suenaga	355	53	
TL	EER	2002/0163629	11/2002	Switkes <i>et al.</i>	355	53	
TL	FFR	2003/0123040	07/2003	Almog	355	69	
TL	GGR	2003/0174408	09/2003	Rostalski <i>et al.</i>	359	642	
	HHR						
	IIR						
	JJR						
	KKR						
	LLR						
	MMR						
	NNR						
	OOR						
	PPR						

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclose	No
TL	QQR	JP 04-305915	10/1992	Japan	Ozeki <i>et al.</i>	X			
TL	RRR	JP 04-305917	10/1992	Japan	Ozeki <i>et al.</i>	X			
TL	SSR	JP 06-124873	05/1994	Japan	Takahashi	X		X	
TL	TTR	JP 07-220990	08/1995	Japan	Fukuda <i>et al.</i>	X			
TL	UUR	JP 10-228661	08/1998	Japan	Kurokawa	X			
TL	VVR	JP 10-255319	09/1998	Japan	Suenaga <i>et al.</i>	X			
TL	WWR	JP 10-303114	11/1998	Japan	Suwa	X		X	
TL	XXR	JP 10-340846	12/1998	Japan	Kudo	X		X	
TL	YYR	JP 2001-091849	04/2001	Japan	Aizaki <i>et al.</i>	X			
	ZZR								

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

TL	AAAR	B.J. Lin, "Drivers, Prospects and Challenges for Immersion Lithography", TSMC, Inc., September 2002			
TL	BBBR	B.J. Lin, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997			

Examiner

Date Considered: 12/2005

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office

Atty.
Dkt. No.

M#

Client Ref.

306781

P-0381.010-US

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: Joeri LOF *et al.*

Appln. No.: ~~Unknown~~ 10/705,816

Filing Date: November 12, 2003

Examiner: ~~Unknown~~ *by Lu* Group Art Unit: ~~Unknown~~ *2020*

Date: November 12, 2003

Page

3

of

3

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
CCC						
DDD						
EEE						

FOREIGN PATENT DOCUMENTS

ORIGINAL PAPER DOCUMENTS							Abstract		Readily Available	
		Document Number	Date MM/YYYY	Country	Inventor Name		Enclosed	No	Enclose	No
	FFFF									
	GGG									

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

TL	HHH	B.J. Lin, "The Paths To Subhalf-Micrometer Optical Lithography", SPIE Vol. 922, Optical/Laser Microlithography (1988), pp. 256-269			
TL	IIIR	G.W.W. Stevens, "Reduction of Waste Resulting from Mask Defects", Solid State Technology, August 1978, Vol.21 008, pp. 68-72	-		
TL	JJJR	S. Owa et al., "Immersion Lithography; its potential performance and issues", SPIE Microlithography 2003, 5040-186, February 27, 2003	-		
TL	KKK	S. Owa et al., "Advantage and Feasibility of Immersion Lithography", Proc. SPIE 5040 (2003)			
TL	LLL	Nikon Precision Europe GmbH, "Investor Relations - Nikon's Real Solutions", May 15, 2003	-		
TL	MMN	H. Kawata et al., "Optical Projection Lithography using Lenses with Numerical Apertures Greater than Unity", Microelectronic Engineering 9 (1989), pp. 31-36	-		
TL	NNN	J.A. Hoffnagle et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", J. Vac. Sci. Technol. B., Vol. 17, No. 6, November/December 1999, pp. 3306-3309			
TL	OOO	B.W. Smith et al., "Immersion Optical Lithography at 193nm", FUTURE FAB International, Vol. 15, July 11, 2003			
TL	PPP	H. Kawata et al., "Fabrication of 0.2µm Fine Patterns Using Optical Projection Lithography with an Oil Immersion Lens", Jpn. J. Appl. Phys. Vol. 31 (1992), pp. 4174-4177			
TL	QQQ	G. Owen et al., "1/8µm Optical Lithography", J. Vac. Sci. Technol. B., Vol. 10, No. 6, November/December 1992, pp. 3032-3036			
	RRR				
	SSS				
	TTT				
	UUU				
	VVV				
	WWW				
	XXX				
	YYY				

Examiner

Date Considered: 12/2005

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

De

Docket Number: 081468-0306525
Client Reference: P-1586.010-US

PATENT APPLICATION



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of

LOF et al.

Group Art Unit: 2882

Application No.: 10/705,816

Examiner: Unassigned

Filed: November 12, 2003

Confirmation No.: 5408

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

January 7, 2005

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
TL	SUWA et al. (Reissue Application of U.S. Patent No. 6,191,429 B1)	10/367,910	02/19/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input type="checkbox"/> Other: stamped receipt card
TL	HOOGEN DAM et al. (081468-0308674)	10/831,370	04/26/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card

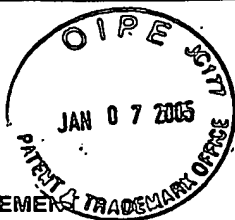
*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

It is respectfully requested that these applications and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent applications is not to be construed as a waiver of secrecy as to those applications now or upon issuance of the present application as a patent.

PLEASE DO NOT PRINT the above information on the patent which results from this application.

Consideration of each listed application is earnestly solicited since unpublished patent applications are contemplated as IDS material; see the exception in Rule 98(a)(2)(iii) and note the penultimate sentence of MPEP 609.

FORM PTÖ-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office



Atty. Dkt. No.	M#	Client Ref.
	306525	P-1586.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: LOF et al.
Appln. No. 10/705,816
Filing Date: November 12, 2003
Examiner: Unknown / 2078 Group Art Unit: 2882

Date: January 7, 2005

Page 1 of 2

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
TL	AR 4,390,273	06/1983	LOEBACH et al.	355	125	
TL	BR 6,603,130	08/2003	BISSCHOPS et al.	250	492.1	
TL	CR 6,633,365	10/2003	SUENAGA	355	53	
TL	DR 2002/0163629	11/2002	SWITKES et al.	355	53	
TL	ER 2003/0123040	07/2003	ALMOGY	355	69	
TL	FR 2003/0174408	09/2003	ROSTALSKI et al.	359	642	
TL	GR 2004/0075895 A1	04/2004	LIN	359	380	
TL	HR 2004/0109237 A1	06/2004	EPPLE et al.			
TL	IR 6,236,634 B1	05/2001	LEE et al.	369	112	
TL	JR 2002/0020821 A1	02/2002	VAN SANTEN et al.	250	492	
TL	KR 2004/0119954	06/2004	KAWASHIMA et al.	355	30	
TL	LR 2004/0125351	07/2004	KRAUTSCHIK et al.	355	53	

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclosed	No
TL	MR JP 04-305915	10/1992	JAPAN	OZEKI et al.	X			
	NR JP 04-305917	10/1992	JAPAN	OZEKI et al.	X			
TL	OR JP 06-124873	05/1994	JAPAN	TAKAHASHI	X		X	
TL	PR JP 07-220990	08/1995	JAPAN	FUKUDA et al.				
TL	QR JP 10-228661	08/1998	JAPAN	KUROKAWA	X			
TL	RR JP 10-255319	09/1998	JAPAN	SUENAGA et al.	X			
TL	SR JP 10-303114	11/1998	JAPAN	SUWA	X		X	
TL	TR JP 10-340846	12/1998	JAPAN	KUDO	X		X	
TL	UR JP 2001-091849	04/2001	JAPAN	AIZAKI et al.	X			
TL	VR JP 07-132262	05/1995	JAPAN	HIRAKAWA et al.	X			

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

TL	WR	B.J. LIN, "Drivers, Prospects and Challenges for Immersion Lithography", TSMC, Inc., September 2002				
TL	XR	B.J. LIN, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997				
TL	YR	S. OWA et al., "Update on 193nm immersion exposure tool", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-51				
TL	ZR	H. HATA, "The Development of Immersion Exposure Tools", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-22				
TL	AAR	T. MATSUYAMA et al., "Nikon Projection Lens Update", SPIE Microlithography 2004, 5377-65, March, 2004				
	BBR					

Examiner: [Signature] Date Considered: 12/2005
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified) To: U.S. Department of Commerce (PW FORM PAT-1449) Patent and Trademark Office					Atty. Dkt. No.	M#	Client Ref.		
					306525		P-1586.010-US		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT					Applicant: LOF et al.				
					Appln. No. 10/705,816				
					Filing Date: November 12, 2003				
					Examiner: Unknown <u>Don Ly</u> Group Art Unit: 2882 <u>2878</u>				
Date: January 7, 2005 Page <u>2</u> of <u>2</u>									
U.S. PATENT DOCUMENTS									
Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)		
	AR								
	BR								
FOREIGN PATENT DOCUMENTS						English Abstract		Translation Readily Available	
		Document Number	Date MM/YYYY	Country	Inventor Name	Enclosed	No	Enclosed	No
TL	CR	JP 58-202448	11/1983	JAPAN	KAWAMURA et al.	X			
TL	DR	WO 2004/019128	03/2004	PCT	OMURA et al.	X		X	
TL	ER	WO 03/077037	09/2003	PCT	ROSTALSKI et al.	X		X	
TL	FR	WO 03/077036	09/2003	PCT	SCHUSTER	X			
TL	GR	DD 206 607	02/1984	GERMANY	WESTPHAL et al.			X	
TL	HR	DD 221 563	04/1985	GERMANY	PFORR et al.			X	
TL	IR	JP 11-176727	07/1999	JAPAN	SHIRASHI		X		
TL	JR	JP 2000-058436	02/2000	JAPAN	FUJISHIMA et al.		X		
TL	KR	WO 2004/053950 A1	06/2004	PCT	OWA		X		
TL	LR	WO 2004/053951 A1	06/2004	PCT	MAGOME et al.		X		
TL	MR	WO 2004/053952 A1	06/2004	PCT	MAGOME et al.		X		
TL	NR	WO 2004/053953 A1	06/2004	PCT	NEI et al.		X		
TL	OR	WO 2004/053954 A1	06/2004	PCT	NEI et al.		X		
TL	PR	WO 2004/053955 A1	06/2004	PCT	HIRUKAWA et al.		X		
TL	QR	WO 2004/053956 A1	06/2004	PCT	NAGASAKA et al.		X		
TL	RR	WO 2004/053957 A1	06/2004	PCT	HIDAKA et al.		X		
TL	SR	WO 2004/053958 A1	06/2004	PCT	MIZUTANI et al.		X		
TL	TR	WO 2004/053959 A1	06/2004	PCT	SHIRAI		X		
TL	UR	WO 2004/053596 A2	06/2004	PCT	GRAUPNER		X		
TL	VR	WO 2004/055803 A1	07/2004	PCT	VAN SANTEN		X		
TL	WR	WO 2004/057589 A1	07/2004	PCT	NEIJZEN et al.		X		
TL	XR	WO 2004/057590 A1	07/2004	PCT	VAN SANTEN et al.		X		
TL	YR	JP 2004-193252	07/2004	JAPAN	Not Available		X		
OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)									
TL	ZR	"Depth-of-Focus Enhancement Using High Refractive Index Layer on the Imaging Layer", IBM Technical Disclosure Bulletin, Vol. 27, No. 11, April 1985, p. 6521							
TL	AAR	A. SUZUKI, "Lithography Advances on Multiple Fronts", EEdesign, EE Times, January 5, 2004							
TL	BBR	B. LIN, "The k_3 coefficient in nonparaxial A/NA scaling equations for resolution, depth of focus, and immersion lithography, J. Microlith., Microfab., Microsyst. 1(1):7-12 (2002)							
	CCR								
Examiner <u>[Signature]</u>					Date Considered: <u>12/2005</u>				
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.									